

PROCEEDINGS OF SPIE

Frontiers in Ultrafast Optics: Biomedical, Scientific, and Industrial Applications XI

**Alexander Heisterkamp
Joseph Neev
Stefan Nolte**
Editors

**23–26 January 2011
San Francisco, California, United States**

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Published by
SPIE

Volume 7925

Proceedings of SPIE, 0277-786X, v. 7925

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Author(s), "Title of Paper," in *Frontiers in Ultrafast Optics: Biomedical, Scientific, and Industrial Applications XI*, edited by Alexander Heisterkamp, Joseph Neev, Stefan Nolte, Proceedings of SPIE Vol. 7925 (SPIE, Bellingham, WA, 2011) Article CID Number.

ISSN 0277-786X
ISBN 9780819484628

Published by

SPIE

P.O. Box 10, Bellingham, Washington 98227-0010 USA
Telephone +1 360 676 3290 (Pacific Time) · Fax +1 360 647 1445
SPIE.org

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